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**SECOND AMENDMENT UNDER 37  
CFR 1.116 EXPEDITED PROCEDURE -  
EXAMINING GROUP 1763**

Box AF  
Assistant Commissioner for Patents  
Washington, D.C. 20231

PATENT  
Attorney Docket No.: 1771X2T19930  
TTC No.: 016301-019930

On April 15, 2002

TOWNSEND and TOWNSEND and CREW LLP

By: [Signature]

#30 HNR  
4/29/02  
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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of:

SEBASTIEN RAOUX et al.

Application No.: 08/988,246

Filed: December 1, 1997

For: METHOD AND APPARATUS FOR  
MONITORING AND ADJUSTING  
CHAMBER IMPEDANCE

Examiner: Rudy Zervigon

SECOND AMENDMENT UNDER 37 CFR  
1.116 EXPEDITED PROCEDURE  
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Sir:

In response to the Advisory Action dated March 15, 2002 in the above-identified application, Applicants respectfully request entry of the Amendment under 37 CFR § 1.116 filed on February 11, 2001, as repeated below.

**IN THE CLAIMS:**

Please amend claims 11, 16, and 20 as follows.

11. A substrate processing system comprising:  
a deposition chamber comprising a reaction zone;